

Amendment
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Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application.

Listing of Claims:

1. (Canceled)
2. (Currently Amended) The phase-shift-mask according to claim 9 ~~claim 1~~, wherein further comprising a third portion of the first pattern that is not transparent ~~[[for]] to light~~.
3. (Currently Amended) The phase-shift-mask according to claim 9 ~~claim 1~~, wherein the first portions have a first width of the first portion extending in a first direction and a first length extending in a second direction that is orthogonal to the first direction, and the second portion has a second width of the second portion extending in [[a]] the first direction between adjacent first portions and a second length extending in the second direction between adjacent first portions, the ratio of the first width to the second width being different from [[1]] unity, and a first length of the first portion and a second length of the second portion extend in a second direction, the second direction being orthogonal to the first direction, the ratio of the first length to the second width length being different from [[1]] unity.
4. (Currently Amended) The phase-shift mask according to claim 9 ~~claim 1~~, wherein each of the first portions of the first pattern is arranged symmetrically ~~are arranged symmetrically~~ about at least one axis.
5. (Currently Amended) The phase-shift mask according to claim 2, wherein each of the first portions of the first pattern is arranged symmetrically ~~are arranged symmetrically~~ about two orthogonal axes.
6. (Currently Amended) The phase-shift mask according to claim 9 ~~claim 1~~, wherein each of the first portions comprises a square, and the second portion comprises a set of four lines bordering and enclosing four sides of the square of each of the first portions.

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7. (Currently Amended) The phase-shift mask according to claim 9 ~~claim 1~~, wherein:
each of the first portions comprises a first sub-pattern being having a U-shape U-shaped;
the second portion comprises a plurality of second sub-patterns each having a U-shape
~~being U-shaped;~~

open ends of the U-shapes of adjacent first and second sub-patterns are orientated
towards each other[.];

each of the first portions comprises a third rectangular sub-pattern, which is enclosed on
three sides by [[the]] an adjacent second sub-pattern of the second portion[.]; and

the second portion comprises a plurality of fourth rectangular sub-pattern, each of which
is enclosed on three sides by [[the]] an adjacent first sub-pattern of the second first portion.

8. (Currently Amended) The phase-shift mask according to claim 9 ~~claim 1~~, wherein the
first and second ~~transmission~~ transmittance are ~~larger~~ greater than 45 percent of the irradiated
light.

9. (New) A phase shift mask, comprising:

first portions arranged in a pattern across the phase shift mask, the first portions having a
first area, a first transmittance of electric field strength of light to be irradiated through the phase
shift mask, and a first phase shift characteristic with respect to light traversing the phase shift
mask through the first portions; and

at least one second portion disposed adjacent the pattern of first portions across the phase
shift mask, the second portion having a second area, a second transmittance of electric field
strength of light to be irradiated through the phase shift mask, the second transmittance being
different from the first transmittance, and a second phase shift characteristic with respect to light
traversing the phase shift mask through the second portion;

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wherein the product of the first area and the first transmittance is substantially equal to the product of the second area and the second transmittance, such that a zero order diffraction of light is substantially absent from light irradiated through the phase shift mask.